SHIGA7.029APC PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Hojo et al.
Appl. No. : 10/553,083

Filed : October 11, 2005

For : POSITIVE RESIST

COMPOSITION AND METHOD

OF FORMATION OF RESIST

PATTERN

Examiner : C. Hamilton

Group Art Unit : 1752

SUBMISSION WITH RCE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **July 3**, **2007**, and the Advisory Action mailed **October 16**, **2007**, Applicants respectfully request the Examiner to enter the following amendments and consider the following remarks.

Amendments to the claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 6 of this paper.